

### New Generation of Fine Pitch Kelvin Spring Probes

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## Introduction

- Wafer-Level-Chip-Scale-Package (WLCSP) is becoming packaging technology of choice across different applications
- Major trends in WLCSP
  - Increasing wafer size
  - Shrinking die size
  - Tighter pitches
  - Increasing I/O counts
- New generation of Kelvin contacting technology is required to support these immutable trends
  - Scales down to very fine pitches and ball sizes
  - Highly precise and reliable
  - Easier to use and maintain (crucial for high I/O count applications that are cost sensitive)



Yannou, J-M.: Market dynamics impact WLCSP adoption, 3D Packages, No. 22, Feb (2012)



WLCSP wafer

## **Goals & Objectives**

#### • Goal:

- Advance True Kelvin Spring Probes for fine-pitch WLCSP
- Objectives
  - Enable True Kelvin measurement over full array at fine pitches
  - Enable capability to "mix and match" w standard spring probes for non-Kelvin test I/Os
  - Improve pointing accuracy for reliably hitting smaller targets
  - Make True Kelvin Spring Probes easier to use and maintain
  - Reduce the overall cost of Kelvin Test

## Why Kelvin Measurement?

#### **Overview:**

- Test interconnect circuit
- Kelvin connection
- Evolution of resistance measurement
  - Traditional Two-Wire measurement
  - Four-Wire measurement through two standard spring probes
  - Four-Wire measurement through two True Kelvin Spring Probes

#### **Test Interconnect Circuit**

- A test interconnect circuit includes test interface board, test contact spring probes, Device-Under-Test (DUT)
- The resistance of the test interface board and the contact probes are added into the resistance measurement, causing significant error in measurement of DUT



## **Improved Measurement Accuracy**

- Direct Measurement vs. Kelvin Measurement
- Direct Measurement (2-wire)
  - In the example, the measurement through one series circuit will measure the total resistance of 2.0 Ω which includes 1.0 Ω from the probes

#### Kelvin measurement (4-wire)

- The Kelvin connection separates the sensing circuit from forcing circuit to create a parallel connections, which measures the voltage with higher accuracy
- In the example, this measurement correctly determines the resistance of DUT as 1.0 Ω

#### **DC Measurement Accuracy at the DUT**

Direct Measurement (2-wire) Setup





# Sensing Circuit Is Not a Big Deal

- The input impedance of the Multimeter is very high and negligible current flows into it
- Sensing circuit is parallel to forcing circuit
- Sense connections are very close to DUT



### **Traditional Two-Wire Interconnect**

- Shown here is a basic block diagram of an Automatic Test Equipment (ATE) measurement circuit with some of the interconnects to the DUT
- The total resistance measured will include the resistance of the test interface board, test contact probes and DUT because there is only one series path for current to flow
- The resistance introduced from the test board and the probes become unacceptable for many applications where DUT resistances are very low



# Four-Wire Measurement through Two Standard Spring Probes

- Four-wire connection at the contactor involves shorting the force and sense lines via the spring probes at the test interface board
  - This method is used when an accurate measurement is desired, but Kelvin contacting <u>at</u> the DUT is not feasible.
  - The voltage and resistances measured are across the combination of contact probes and DUT



# Four-Wire Measurement through Two True Kelvin Spring Probes

 The True Kelvin Spring Probe consists of two isolated electrical paths in one probe, allowing accurate measurement right at the DUT



# Design Criteria for True Kelvin Spring Probes

- True Kelvin spring probe should have force and sense paths integrated into a single probe
- Force and sense paths should be electrically isolated from one another
- Probe should have two tips one for force and one for sense
  - Each tip is allowed to move mechanically independent of other so they can conform to ball non-uniformities
- Tip dimensions and probe pointing accuracy should allow hitting small targets (ball diameters < 200 µm)</li>
  Electrical and mechanical performance should meet application specs





#### **MEMS Additive Manufacturing Overview**

Sample devices



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## **Additive Manufacturing of Kelvin Probes**

- Complex 3D structure and assembly can be additively fabricated
  - Enables fabrication of the full True Kelvin Spring Probe without the need of assembly
- Different metals, metal alloys, and dielectric material can be combined into micro-composite structures
  - Enables optimized electrical and mechanical characteristic for the True Kelvin spring probe
- High accuracy and high precision achieved using MEMS processes
  - Enables precise spring and tip geometry for advance pitch applications



## Results

 True Kelvin Spring Probes designed and fabricated using MEMS additive manufacturing technology

#### Salient features:

- Designed for < 350 μm pitch</li>
- Spacing between tips: 40 µm
- Force and sense paths verified to be electrically isolated
- Tips verified to move independently
- Demonstrated lifetime of probe > 1M cycles
- Designed to require only 1 hole per probe in the socket



## Summary

- Kelvin measurement eliminates parasitic voltage drops which degrade the measurement accuracy when the user is seeking to calculate very low resistance values and obtain higher confidence in test data
- New Generation of Fine-Pitch True Kelvin Spring Probes provide a solution to meet the requirements advanced WLCSP applications
  - Leverages highly flexible additive manufacturing technology
  - Enables Kelvin testing at fine pitches & high I/O count
  - Promises high performance, reliability at lower overall cost



# **Thank You**

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